Neha Thakur

List of Publications by Year
in descending order

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12 papers	127 citations	1163117 8 h-index	1281871 11 g-index
12 all docs	12 docs citations	12 times ranked	92 citing authors

#	Article	IF	Citations
1	Direct Patterning of CsPbBr₃ Nanocrystals via Electron-Beam Lithography. ACS Applied Energy Materials, 2022, 5, 1672-1680.	5.1	8
2	Fluorine-Rich Zinc Oxoclusters as Extreme Ultraviolet Photoresists: Chemical Reactions and Lithography Performance. ACS Materials Au, 2022, 2, 343-355.	6.0	9
3	Role of low-energy electrons in the solubility switch of Zn-based oxocluster photoresist for extreme ultraviolet lithography. Physical Chemistry Chemical Physics, 2021, 23, 16646-16657.	2.8	15
4	Bottom-Up Nanofabrication with Extreme-Ultraviolet Light: Metalâ€“Organic Frameworks on Patterned Monolayers. ACS Applied Materials & Interfaces, 2021, 13, 43777-43786.	8.0	5
5	Fluorescent Labeling to Investigate Nanopatterning Processes in Extreme Ultraviolet Lithography. ACS Applied Materials & Interfaces, 2021, 13, 51790-51798.	8.0	10
6	Mixed-ligand zinc-oxoclusters: efficient chemistry for high resolution nanolithography. Journal of Materials Chemistry C, 2020, 8, 14499-14506.	5.5	11
7	Universal direct patterning of colloidal quantum dots by (extreme) ultraviolet and electron beam lithography. Nanoscale, 2020, 12, 11306-11316.	5.6	27
8	Photon-induced Fragmentation of Zinc-based Oxoclusters for EUV Lithography Applications. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2020, 33, 153-158.	0.3	5
9	Stability studies on a sensitive EUV photoresist based on zinc metal oxoclusters. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2019, 18, 1.	0.9	19
10	Zinc-based metal oxoclusters: towards enhanced EUV absorptivity. , 2019, , .		2
11	Heavy metal incorporated helium ion active hybrid non-chemically amplified resists: Nano-patterning with low line edge roughness. AIP Advances, 2017, 7, 085314.	1.3	12
12	New non-chemically amplified molecular resist design with switchable sensitivity for multi-lithography applications and nanopatterning. Journal of Micromechanics and Microengineering, 2017, 27, 125010.	2.6	4